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EXHIBIT 1

Best available coly

Summary

Objective:

To evaluate, and compare, defect performance of four different brushes, under the same environment.

Tool used:

. 300MM Mirra Messa,

Results:

BPTone 212XP material (3920-00307) had the best particle removal rate,

Experimental Details For Tool Qualification

Tools

- S3 300mm Mirra-Mesa
- Megasonics
 - Brush 1
- **Brush 2**
- SRD
- **Metrology**
- KLA-Tencor
- Oxide BKM recipe

Methodology

- Cycle 100 dummy wafers through the system daily
- Festfire 4 oxide defect wafers
- Defect Qualification is < 30 adders (delta = post pre) at 0,13 μm
- Cleaning Performance Metrics;
- Delta = precount postcount (typically used at customer site)
- Map-to-map defect analysis not available

Experimental Details for Brush Type Evaluation

Methodology

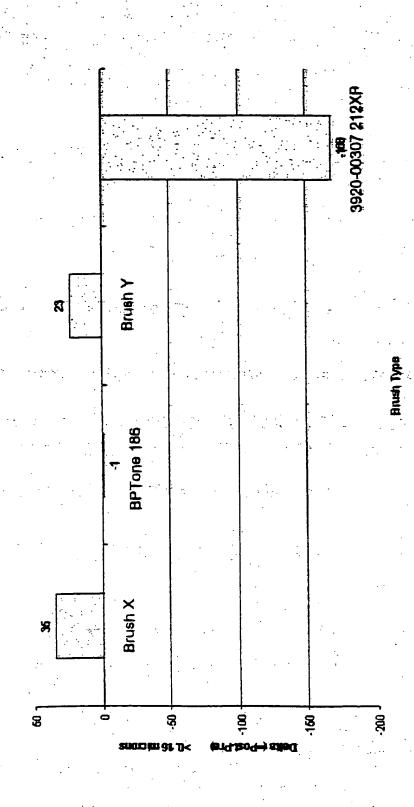
- Install Brushes and Run Brush Break-in twice
- Cycle 25 dummy wafers through system
- Testfire 4 oxide defect wafers for qualification
- Defect Qualification is < 30 adders (delta = post pre) at 0,13 μm
- Testfire 5+ oxide defect wafers for Using BKM 1.1
- · Cleaning Performance Metrics:
- Delta = precount postcount (typically used at customer site
- Map-to-map defect analysis not available

Objective

Evaluate Four Different Brushes for Brush Module 2

- Brush types
- Brush X
- Brush Y
- BPT-1 Type 186
- 3920-00307, BPT-1 Type 213

Effect of Different Brush Types



BPT-1 Type 212 Brushes Has Best Defect Performance

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